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20. ABSTRACT (Cont.)

 Mechanisms and Kinetics of the Isomerizations and Decompositions of Organosilylenes.

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 From the above studies, we were able to propose a general reaction mechanism for carbosilane production from the decomposition of dimethylsilane (paper #12).

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AFOSR-TR- 88-0520

FINAL PROJECT REPORT (AFOSR-83-0209)

1. SUMMARY OF WORK

Our AFOSR research has focused on three important areas of organosilicon chemistry as that chemistry relates to the formation and production of carbosilanes:

<u>Area #1</u>) Mechanisms and Kinetics of the Decompositions of Silane and Organosubstituted Monsilanes, and of Disilane and Organosubstituted Disilanes.

Systems investigated were n-propylsilane¹, ethylsilane², silane^{3,4}, dimethylsilane^{5,12},

ethynylsilane⁶, butylsilane⁷, chloromethyldimethylsilane⁸, and 1,1,2,2-tetramethyldisilane¹³,

1,1,2-trimethyldisilane¹⁴ and 1,1-dimethyldisilane¹⁵.

Results of area #1 studies: The main findings of these studies were:

1) The decomposition kinetics of monosubstituted silanes (RSiH₃), are independent of the nature of the R group, (A-factors $\approx 10^{15.2\pm0.2}$ sec⁻¹ and E₂ $\approx 64\pm1$ Kcal).

2) The primary dissociation reaction channel of $RSiH_3$ compounds is 1,1 H₂ elimination (rxn 1).

3) RH elimination (rxn 2) also occurs (when $R = CH_3$ and perhaps also C_2H_3 and phenyl) but does not compete with H₂ elimination

4) Decompositions of dialkylsilanes and monoalkylsilanes ($R > CH_3$) are accelerated by silylene induced chain reactions (e.g. rxns 3-6, for ethylsilane).

5) Free radical chain reactions, in addition to silylene chains, occur in the decompositions of dialkyl and higher alkylsubstituted monosilanes.

6) Alkyl substitution for H in monosilanes increases decomposition activation energies by about 4 ± 1 Kcal/R group up to R₂SiH₂ (i.e. the order of thermal stabilities in monosilanes is SiH₄ < RSiH₃ < R₂SiH₂ \approx R₃SiH).

7) Disilanes decompose mainly by 1,2 H shifts (e.g. rxn 7), but 1,1 H_2 eliminations become important at higher temperatures (e.g. rxn 8).

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8) Decompositions by 1,2 H₂ eliminations (e.g. rxn 9) do not occur.

Alkylsilane Decompositions

RSiH₃ --¹ RSiH + H₂ RSiH₃ --² RH + SiH₂ RSiH₃ --³ C₂H₄ + SiH₂ SiH₂ + RSiH₃ --⁴ RSiH₂SiH₃ RSiH₂SiH₃ --⁵ RSiH + SiH₄ RSiH ---6--> olefin + SiH₂ Alkyldisilane Decompositions Illustrated for a 1.1-alkyldisilane

 $RSiH_{2}SiH_{2}R - \xrightarrow{9} RSiH_{3} + SiH_{2} \qquad 1,2 \text{ H-shift}$ $-\xrightarrow{9} RSiH_{2}SiR + H_{2} \qquad 1,1 \text{ H}_{2} \text{ elimination}$ $X - \xrightarrow{9} - \xrightarrow{9} RSiH = SiHR + H_{2} \qquad does \text{ not occur}$

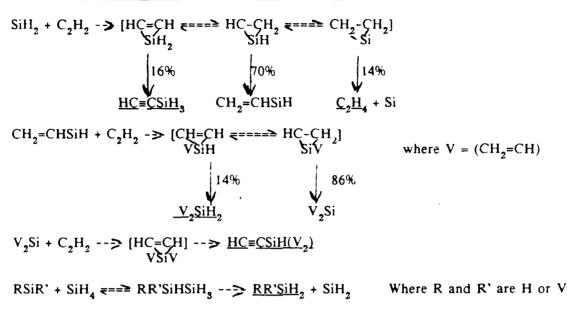
Area #2) Relative Rate Kinetics of the Trapping Reactions of SiH₂.

<u>Systems studied</u> were silvlene reactions with ethylene and butadiene¹⁰, silvlene reactions with MeOH and butadiene⁹, silvlene reactions with acetylene and silane⁴, and silvlene reactions with 1-butene and silane¹¹. Systems under investigation are SiH₂ with 1-pentene and cis-2-butene. Results of the area #2 relative rate studies were:

1) Silylene trapping by multiple bonded substrates are complex processes involving multiple reaction channels, some of which do not produce observable products. For example silylene trapping by acetylene and silane is non-quantitative and mass balances of the observable products, which are disilane, vinylsilane, ethynlsilane, ethylene, ethynlvinylsilane and ethynldivinysilane, diverge increasingly from theoretical as the reaction proceeds. The mechanism, which involves silacyclopropane formations and subsequent isomerizations and decompositions, is shown in Scheme 1 below. [Observed products are underlined.]

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Scheme I: Mechanism of the Silvlene + Acetylene Reaction



2) Trapping by ethylene and other olefins is similarly complex. The corresponding mechanism shown below in Scheme II:

Scheme II: Mechanism of the Silvlene + Ethylene Reaction

$$SiH_{2} + C_{2}H_{4} \equiv = \Rightarrow H_{2}C-CH_{2} \equiv \Rightarrow CH_{3}CH_{2}SiH$$

$$H H \equiv = \Rightarrow CH_{2}=CHSiH_{3}$$

$$CH_{3}CH_{2}SiH + C_{2}H_{4} \equiv = \Rightarrow CH_{2}-CH_{2} \equiv \Rightarrow (CH_{3}CH_{2})Si:$$

$$H C_{2}H_{5} \equiv \Rightarrow CH_{2}=CHSiH_{2}C_{2}H_{5}$$

The intermediate silylenes of the above reaction $(SiH_2, C_2H_5SiH \text{ and } (C_2H_5)_2Si)$ can be trapped by Si-H insertion trapping agents to eventually produce alkylated silanes. Also, on the basis of poor product mass balances, it is clear that continued trapping by ethylene leads not only to vinylsilane products but more importantly to polymeric materials. Solid deposits on the reaction cell walls and connecting inlet and outlet tubes are further evidence for polymer formation.

3) Relative rate constant determinations for silvlene trapping reactions by various substrates have been determined, and the relevant reactions and their kinetics are shown below.

Competing Reactions

Relative Kinetics

 $SiH_{2} + C_{4}H_{6} - 10 \Rightarrow SiH_{2} + C_{4}H_{6} - 10 \Rightarrow SiH_{2} + C_{4}CH$ $SiH_{2} + MeOH - -11 \Rightarrow MeOSiH_{3}$ $SiH_{2} + C_{2}H_{2} - -12 \Rightarrow HC \equiv CSiH_{3}$ $SiH_{2} + 1 - butene - -13 \Rightarrow all products$ $SiH_{2} + SiH_{4} - -14 \Rightarrow Si_{2}H_{6}$

$$\ln(k_{10}/k_{11}) = 5.9 - 5846 \text{ cal/RT}$$

 $\ln(k_{10}/k_{12}) = 1.5 - 712 \text{ cal/RT}$

 $k_{18}/k_{14} = 2.1 \ (643-689 \ \text{K})$

<u>Area #3</u>) Mechanisms and Kinetics of the Isomerizations and Decompositions of Organosilylenes.

<u>Systems studied</u> were the isomerization and decomposition kinetics of ethylsilylene², npropylsilylene¹, ethynlsilylene⁶, and most importantly, n-butylsilylene⁷, and sec-butylsilylene¹¹]. <u>Results</u> of the area #3 studies are:

1) Alkysilylenes (R > Me) decompose at SPST and static system reaction temperatures to SiH₂ and olefins.

2) The mechanism of decomposition involves silacyclopropane intermediates (or perhaps at SPST temperatures, silacyclobutanes).

3) Alkylsilylene decompositions have activation energies less than 30 K cal.

4) The decomposition of sec-butylsilylene occurs with an activation energy significantly lower than its decomposition reaction enthalpy. This requires a very loose transition state for the decomposition reaction and also requires that the decomposition occur by a consecutive step process (e.g. a biradical mechanism).

5) Silylenes add very readily to pi bonds to form very labile silacyclopropanes. These addition reactions are high A-factor processes, probably consecutive step biradical processes, and cannot be, as formally believed, single step concerted processes.

6) Silacyclopropanes have three important and competing reaction pathways: decomposition to silylene and olefin, isomerization to a silylene via an H atom shift from silicon to carbon and

isomerization to a vinylsilane via an H atom shift from carbon to silicon.

7) Alkylsilylenes readily isomerize via intramolecular C-H insertion reactions. The 3-center insertions producing silacyclopropanes are the most facile and are the dominant reactions at 'low' temperatures. Higher center insertions, (e.g. four center to produce silacyclobutanes, and five center to produce silacyclopentanes) appear to occur only under 'high' temperature shock tube reaction conditions. Thus in the reactions of n-butylsilylene generated at shock tube temperatures (i.e. $T \approx 1200$ K), see Scheme III, the rate constant ratios for 3-center/4-center/5-center reactions were calculated on the basis of product yields to be $k_{3-center}/k_{4-center}/k_{5-center} = 1/0.3/1.^7$

Scheme III: n-Butylsilylene Isomerization and Decomposition Rxns

n-BuSiH > EtCH-CH ₂ > CH ₃ CH ₂ CH=CH ₂ + SiH ₂ SiH ₂
SIH ₂
$CH_3CH_2CHCH_3 \leftarrow CH_3CH-CHCH_3 \leftarrow CH_3CH=CHCH_3 + SiH_2$ SiH
SIH SIH ₂

 $CH_3CHCH_2CH_2 \rightarrow CH_3CH=CH_2 + CH_2=SiH_2$ $I_{-----}SiH_2$

2. PROGRESS TOWARD UNDERSTANDING THE DETAILS OF THE MECHANISM FOR CARBOSILANE FORMATION FROM ALKYSILANE PYROLYSES.

From the above studies, we have managed to learn enough about the general reaction and kinetic behaviors of the important intermediates and reactive products produced in organosilicon pyrolysis reaction systems to be able to propose a general reaction mechanism for carbosilane production.¹² Thus a mechanism, shown in part in Scheme IV, has been presented relative to the dimethylsilane pyrolysis system. This mechanism explains both qualitatively and semiquantitative the complex of products formed in that system (including 4-membered, 6-membered and 6-membered polycyclic adamantane type carbosilane products). Thus modeling

predictions with regard to the nature and yield of products are in good agreement with the experimental data.

Scheme IV: Mechanism of the Dimethylsiiane Pyrolysis

$$Me_2SiH_2 - -45 \Rightarrow Me_2Si + H_2$$

 $Me_2Si + Me_2SiH_2 = = Me_2HSiSiHMe_2$
 $Me_2Si + Me_2HSiSiHMe_2 - --47 - \Rightarrow Me_2Si=SiMe_2 + Me_2SiH_2$
 $Me_2Si=SiMe_2 = = = Me_3SiSiMe$
 $Me_3SiSiMe - -49 \Rightarrow Me_2Si-SiMeH = = = Me_2SiHCH_2SiMe - -51 \Rightarrow MeHSi SiHMe CH_2$
 $f_2 = Me_3SiCH_2SiH - -53 \Rightarrow Me_2Si SiH_2$
 $Me_2SiHCH_2SiMe + Me_2SiH_2 - ---> rxns like 45-53 to trisilahexanes & tricyclohexanes
 $Me_3SiCH_2SiH + Me_2SiH_2 - ---> rxns like 45-53 to trisilahexanes & tricyclohexanes$$

3. OTHER RECENTLY COMPLETED RESEARCH AND OTHER ONGOING RESEARCH

There are several projects still in progress which have been supported by AFOSR. These projects fall under the three research areas described previously and will produce results that are quite significant to those areas. Among these are the kinetic studies on 1,1,2trimethyldisilane¹⁴, 1,1-dimethyldisilane¹⁵ and 1,1,2,2-tetramethyldisilane.¹³ The data from these studies will be used to resolve long standing problems concerning the heats of formation of alkylated disilanes, and even more important, heats of formation of alkylated silylenes.¹⁶ Preliminary calculations for the latter give $\Delta H^{\circ}_{t}(MeSiH) \approx 48$ Kcal/mol and $\Delta H^{\circ}_{t}(Me_{2}Si) \approx 34$ K.cal/mol. In addition, the heat of formation of hexamethyldisilane is calculated to be about -78 Kcal/mol, a value in agreement (within the experimental errors) of the -81 Kcal/mol value deduced from the decomposition kinetics of hexamethyldisilane as reported by Davidson et.al. This work¹⁶, when coupled with other available and reliable literature data, will also result in a revised additivity scheme for the accurate estimation of the thermodynamic properties of C,H,and Si containing compounds.¹⁷

Work continues on studies of the intramolecular rearrangements and decompositions of long chain alkylsilylenes, where the latter are generated via silylene additions to long chain olefins. The results of these studies will supplement our understanding of alkysilylene reactions and hopefully clarify the kinetics of their elementary reactions (i.2. their intramolecular insertions, ring openings and decompositions). Thus, for example, while reasonable estimates of the rate constants for intramolecular 3,4,5 and 6 membered ring formations can be made (i.e. such estimates have been used successfully in the various modeling studies mentioned in this report) no direct and unambiguous data have yet been gathered for these reactions. This has been, and will continue to be, one of the main focuses of our ongoing research with or without AFOSR support. A complete knowledge of carbosilane formation kinetics will not be possible until the kinetics of these kinds of reactions are fully understood.

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